

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Narwankar et al.

Application No.: 10/772,893

Filed: February 4, 2004

For: TAILORING NITROGEN PROFILE  
IN SILICON OXYNITRIDE USING  
RAPID THERMAL ANNEALING WITH  
AMMONIA UNDER ULTRA-LOW  
PRESSURE

Examiner: Kelly M Stouffer

Art Unit: 1762

Confirmation No.: 5371

Mail Stop RCE  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

**PRELIMINARY AMENDMENT**

Dear Examiner:

This is in response to the Final Office Action mailed February 25, 2008 (and the Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 filed concurrently herewith). Applicants respectfully request the Examiner to enter this Amendment and consider the following remarks.

**The Listing of Claims** begins on page 2 of this paper.

**Remarks/Arguments** begin on page 12 of this paper.

I hereby certify that this correspondence is being deposited via  
EFS Web on the date below:

May 16, 2008

\_\_\_\_\_  
Date of Deposit

/Justin K. Brask/

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Justin K. Brask, Reg. #61,080